

L Number	Hits	Search Text	DB	Time stamp
1	80	(((resist or photoresist) with round\$3) and etch\$4) and "ion beam"	USPAT; EPO; JPO; DERWENT; IBM TDB	2004/05/05 09:58
2	862	((resist or photoresist) with round\$3) and etch\$4	USPAT; EPO; JPO; DERWENT; IBM TDB	2004/05/05 09:58
3	81	(MEMS or "micro electromechanical system") and ((pattern\$3 or mask\$4) with round\$3)	USPAT; EPO; JPO; DERWENT; IBM TDB	2004/05/05 10:02
4	1481	(MEMS or "micro electromechanical system") same (mating or actuator)	USPAT; EPO; JPO; DERWENT; IBM TDB	2004/05/05 10:03
5	152	(MEMS or "micro electromechanical system") same (mating or actuator) same (pattern\$4 or mask\$3)	USPAT; EPO; JPO; DERWENT; IBM TDB	2004/05/05 10:37
6	8	(MEMS or "micro electromechanical system") same (mating) same (pattern\$4 or mask\$3)	USPAT; EPO; JPO; DERWENT; IBM TDB	2004/05/05 10:27
12	1		USPAT	2004/05/05 10:32
13	23	(MEMS or "micro electromechanical system") same (mating or actuator) same (slider)	USPAT; EPO; JPO; DERWENT; IBM TDB	2004/05/05 10:41
14	3	(MEMS or "micro electromechanical system") same (slider) same pattern\$4	USPAT; EPO; JPO; DERWENT; IBM TDB	2004/05/05 10:42
15	175	(MEMS or "micro electromechanical system") and (slider) and pattern\$4	USPAT; EPO; JPO; DERWENT; IBM TDB	2004/05/05 10:43